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(54) **Title:** POLISHING PAD FINISHING APPARATUS

(54) 发明名称: 一种抛光垫修整装置

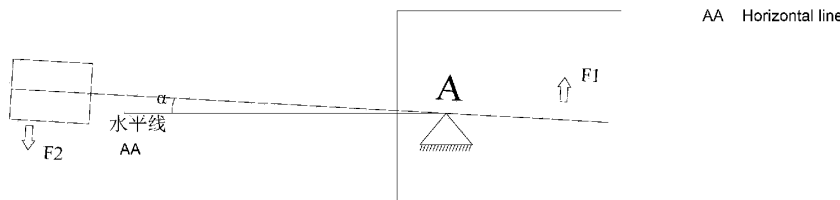


图 1

(57) **Abstract:** Disclosed in the present invention is a polishing pad finishing apparatus, comprising: a connecting arm that horizontally extends; a finishing head unit, provided at one end of the connecting arm and used for finishing a polishing pad; and a base unit, provided at the other end of the connecting arm, movably connected to the connecting arm, and used for driving the connecting arm to drive the finishing head unit to vertically move up and down, so that the finishing head unit is close to or far away from the polishing pad in a direction tending to be perpendicular to the polishing pad. The present invention can stably achieve uniform and stable positive pressure in a finishing process and ensure the consistency of a polishing finishing process; the apparatus is not a motion amplification mechanism, and can effectively reduce the impact effect of the finishing head unit on the polishing pad in the process of moving to the polishing pad; and no amplification effect is realized, and the consistency of the working station state of the finishing head unit is more easily ensured.

(S7) 摘要: 本发明公开了一种抛光垫修整装置, 包括: 连接臂, 水平延伸; 修整头单元, 设于连接臂的一端, 用于修整抛光垫; 基座单元, 设于连接臂的另一端, 与连接臂活动连接, 用于驱动连接臂带着修整头单元垂直上下移动, 以使得修整头单元沿趋于垂直的方向靠近或远离抛光垫。本发明可以稳定实现修整过程中的均匀稳定的正压力, 保证了抛光修整过程的一致性; 不是一个运动放大机构, 可以有效减轻修整头单元在运动至抛光垫过程中对抛光垫的冲击作用; 无放大作用, 更容易保证修整头单元工位状态的一致性。

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(84) 指定国 (除另有指明, 要求每一种可提供的地区保护): ARIPO (BW, CV, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, ST, SZ, TZ, UG, ZM, ZW), 欧亚 (AM, AZ, BY, KG, KZ, RU, TJ, TM), 欧洲 (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, ME, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG)。

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